



SWTEST

PROBE TODAY, FOR TOMORROW

2023 CONFERENCE

Fully Automated Integrated Silicon Photonic Wafer Test



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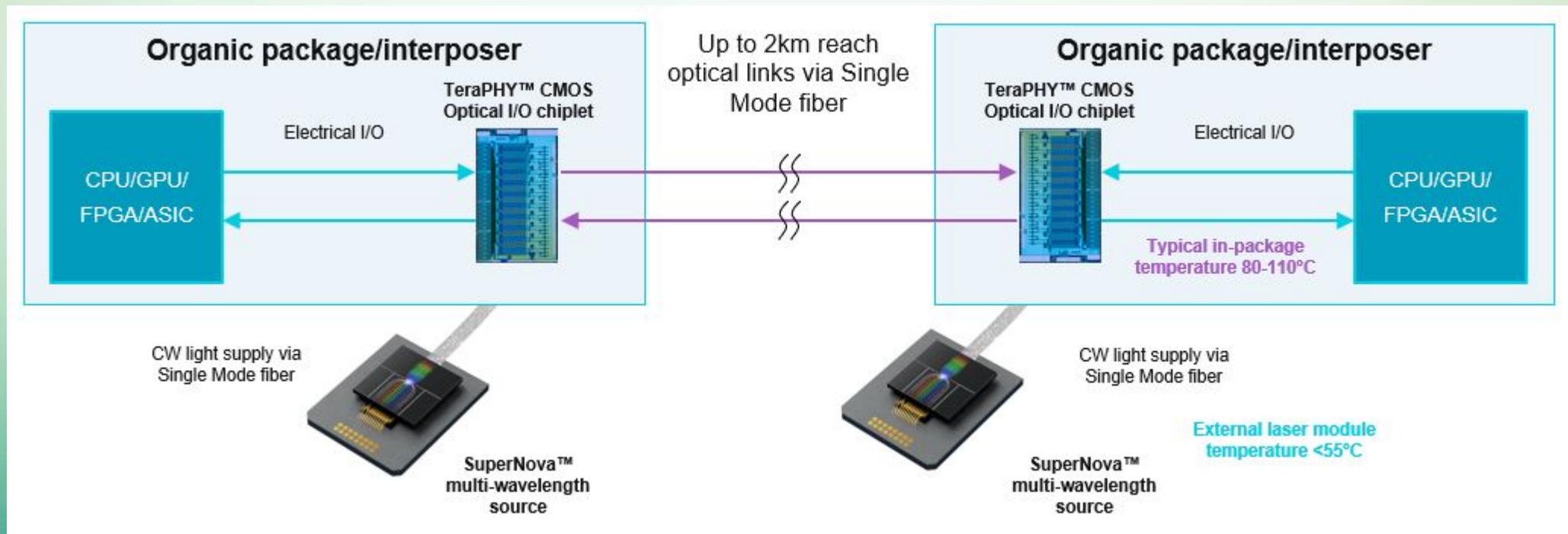
June 5 - 7, 2023

Overview

- **Introduction to Ayar Labs**
- **Early Characterization Setup**
- **FormFactor CM300-Silicon Photonics Probe Station**
 - Overview of Test Executor
 - Improving Test Throughput
- **Improved Test Flow**
- **Current Work: Low Loss Wafer Level Edge Coupling**
- **Future Work: Probe Card for Wafer Level Electrical-Optical Probing for KGD**

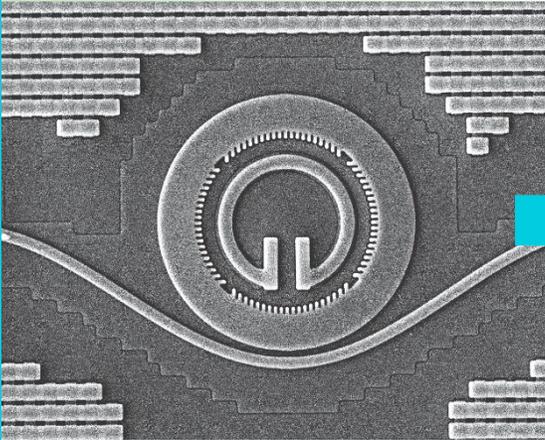
Introduction

- Ayar Labs develops monolithic optical I/O chiplets (TeraPHY™) to enable high bandwidth, low latency, and low power consumption interconnects for chip-to-chip communication
- Applications
 - High performance computing
 - Disaggregated memory/compute architectures



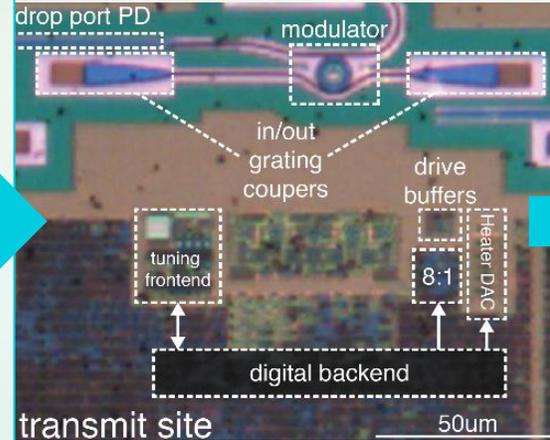
Technology

Micro-ring Resonators



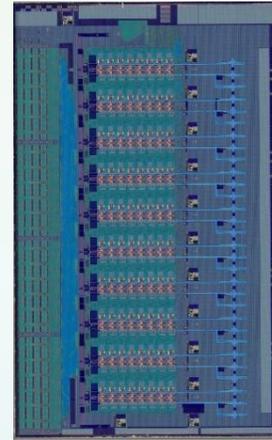
- Up to 1,000x smaller than optical devices in traditional ethernet transceivers
- High-speed capability
- Compatible with high volume 300mm CMOS¹

Monolithic Integration



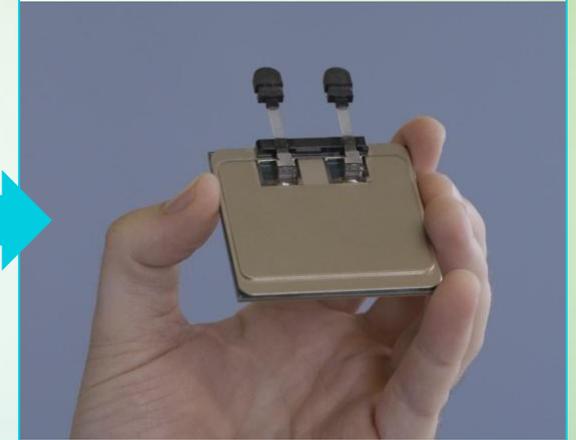
Dense integration of all electronics (TIAs, drivers, equalization, control) and photonics (waveguides, modulators, detectors) on a single CMOS chip

Optical I/O chiplets



- TeraPHY™ chiplet for in-package optical I/O
- Multi-Tbps with <math>< 5\text{pJ/bit}</math>
- Nanosecond latency (no FEC required)

SoC In-Package Integration

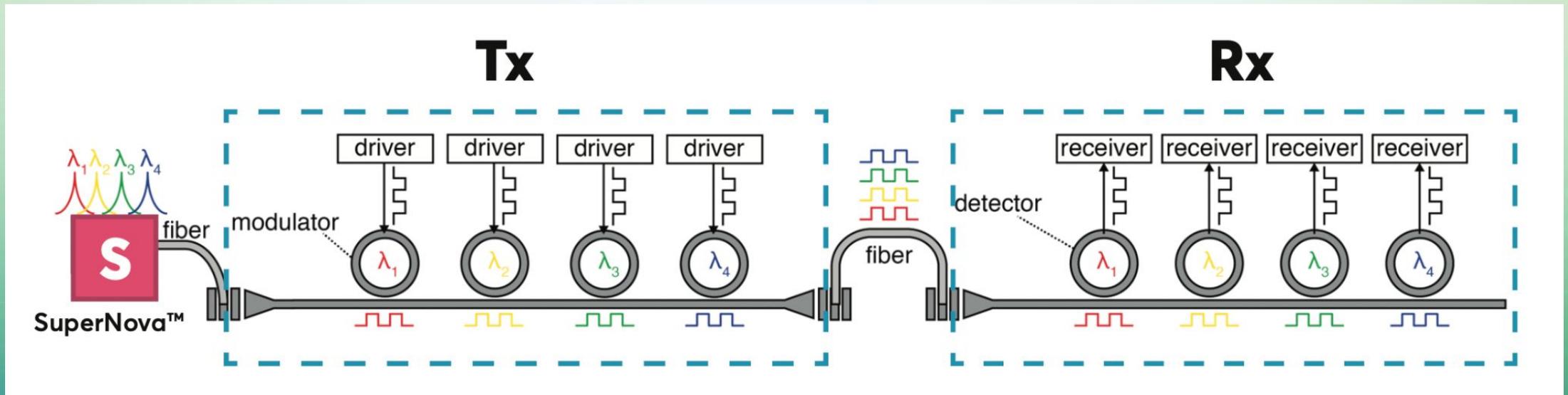


- Integration with state-of-the-art FPGA
- Direct from the package optical I/O

¹ <https://gf.com/gf-press-release/globalfoundries-announces-next-generation-silicon-photonics-solutions-and/>

Technology

- Multi wavelength laser source for encoding data on multiple streams simultaneously
- Tunable microring modulators modulate transmission of specific laser wavelengths based on electrical data pattern input
- Microring resonators on receiver demuxes incoming data on specific wavelengths for conversion to electrical data pattern output

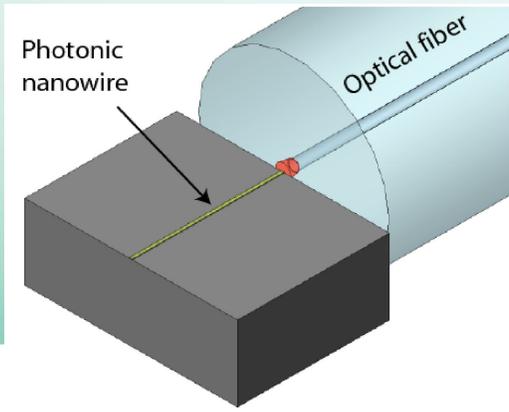


Technology

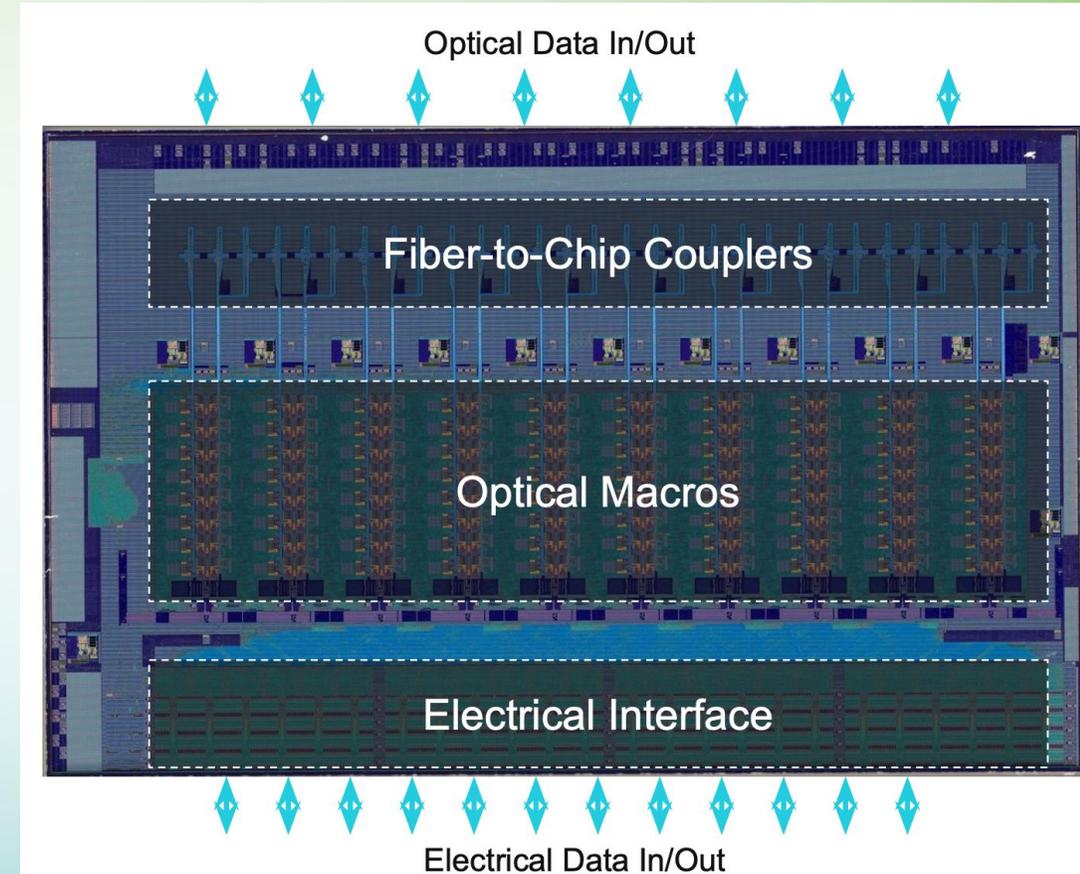
- Reticle contains product and test chips
 - Product chip
 - Horizontal edge couplers for optical connectivity
 - 1400 bumps for electrical connectivity
 - How do we screen for known good die?
 - Electrical wafer sort on standard 93k ATE



Traditional VLSI probe card -> no optical connectivity

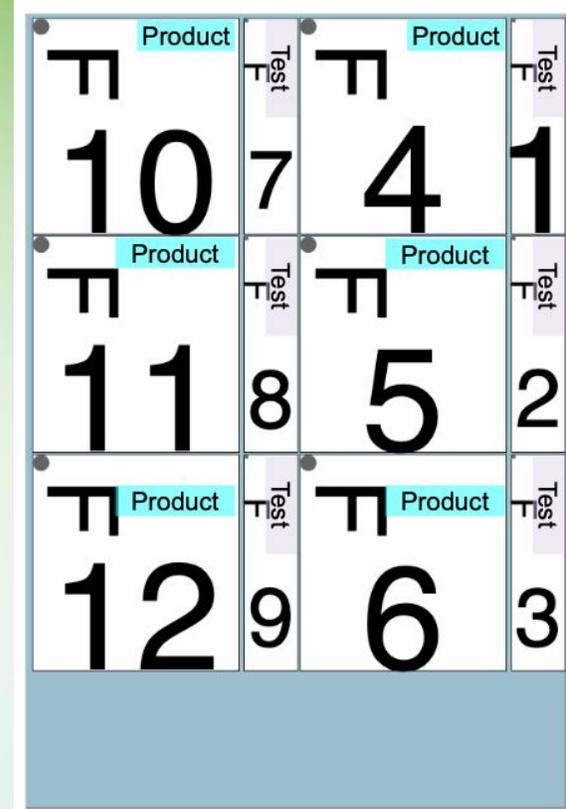


Horizontal edge coupler



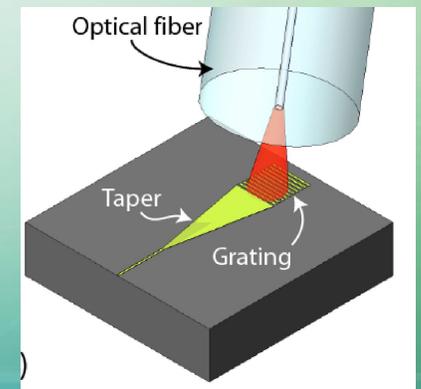
Technology

- Optical link is composed of multiple electronic + photonic components
- During NPI, we had test chips alongside product chips which contain independent device sites using vertical surface couplers
 - Microring resonators (MRR)
 - Tx modulators (doped junction for electro-optic response)
 - Rx ring filters to select particular wavelength
 - Germanium photodetectors
 - Waveguides, NxN optical couplers, polarization splitter/rotators
 - Thermal phase shifters
- Detailed high volume characterization of the components above is used to build a link model and estimate yield of product



NOTCH

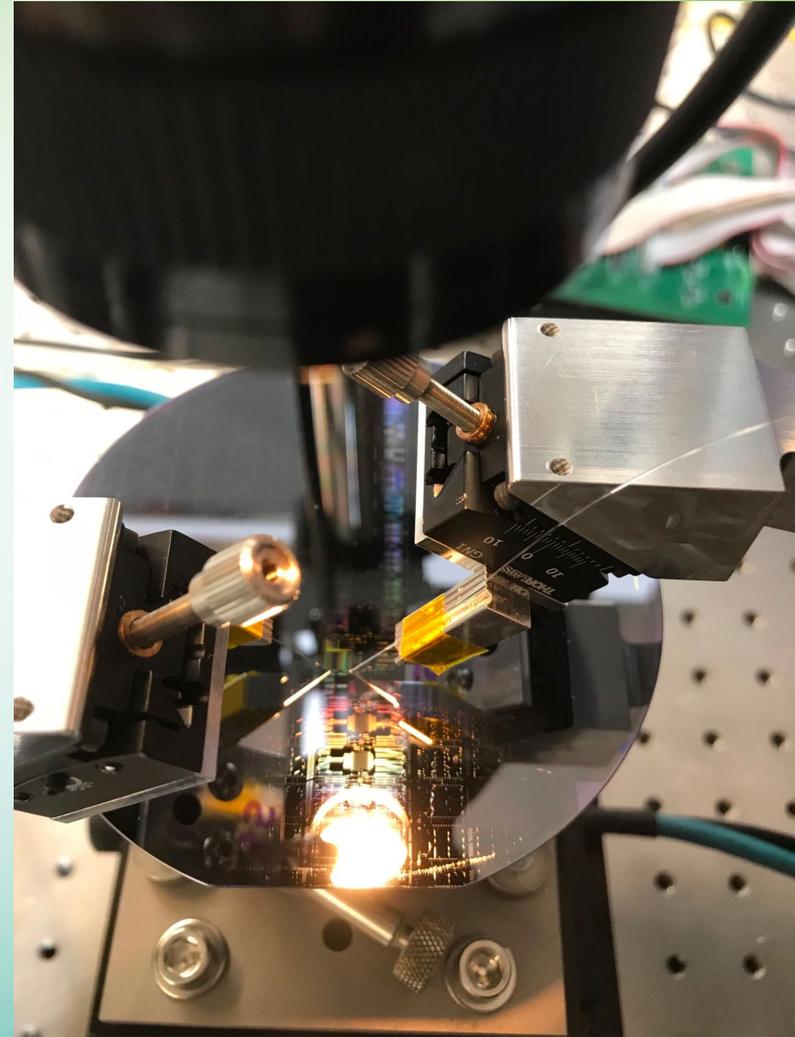
Reticle Plan



Vertical surface coupler

Early Characterization Setup

- **Manual test station**
 - Issues with repeatability and stability of two fiber setup (~ 0.5 dB)
 - Low throughput due to time it takes to align fibers after stepping them from site to site
 - Difficult to accurately set fiber height
 - No testing over temperature



CM300xi - SiPh Probe Station

- Enables automated full wafer optical + electrical characterization of various components that are used to build the TeraPHY™ chiplet
- Repeatable fiber alignment (~0.1 dB)
- Enables testing at high temperature (up to 150°C)



CM300xi - SiPh Probe Station



probe station

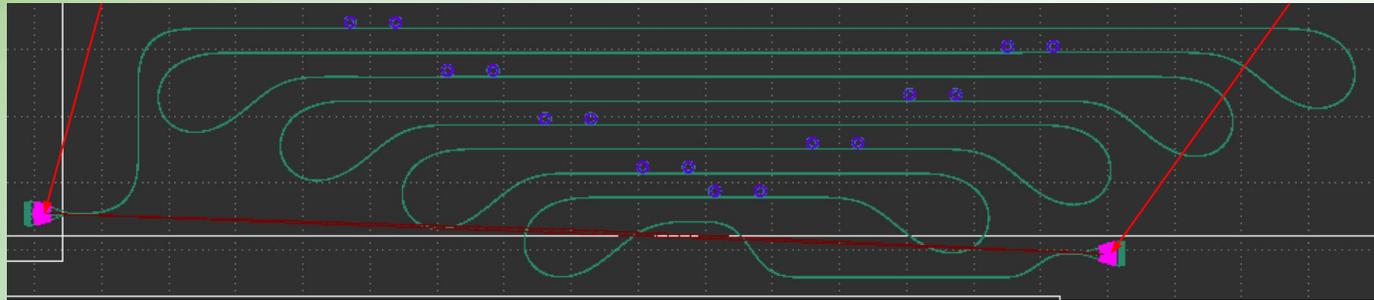
- Enables automated full wafer optical + electrical characterization of various components that are used to build the TeraPHY™ chiplet
 - Keysight swept laser system (Mueller matrix)
 - Optical switches
 - Polarization stabilizer
 - Variable optical attenuator
 - O-band amplifier
 - Optical backscatter reflectometer
 - PCB to enable fiber alignment using photodetector current from DUT on wafer
 - Source measure units
 - Keysight PXI network analyzer (up to 53 GHz)
 - Thorlabs reference transmitter (up to 65 GHz)
 - Bit error rate tester and pattern generator remote head (up to 32 GBaud)
 - Keysight sampling oscilloscope

Examples of Test Sites

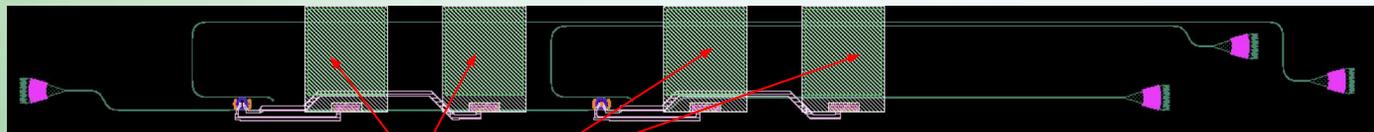
Input
Grating
Coupler

Passive

Output
Grating
Coupler

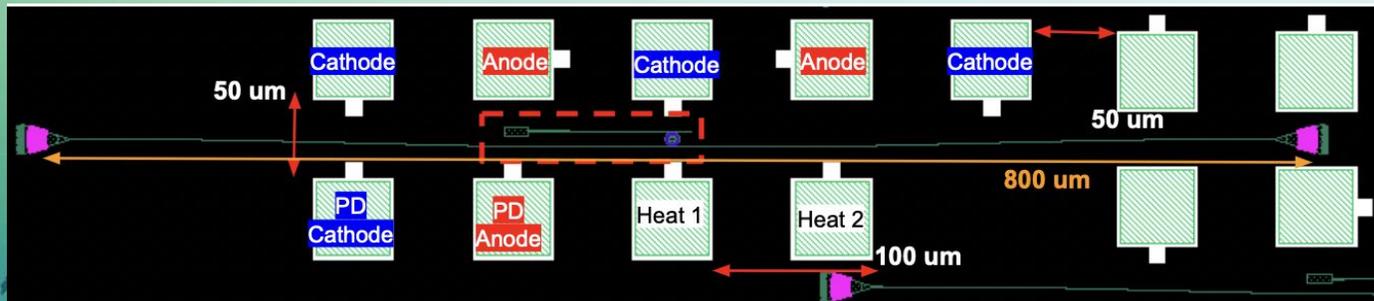


DC Electro Optic

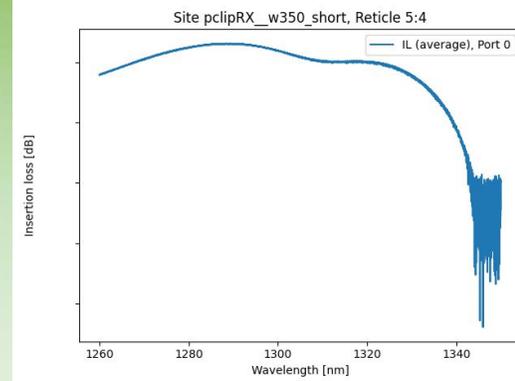


DC pads

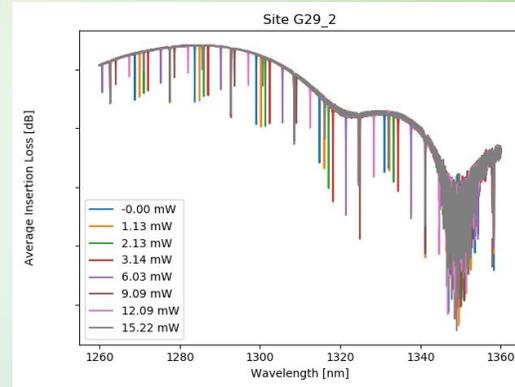
RF+DC Electro Optic (modulator)



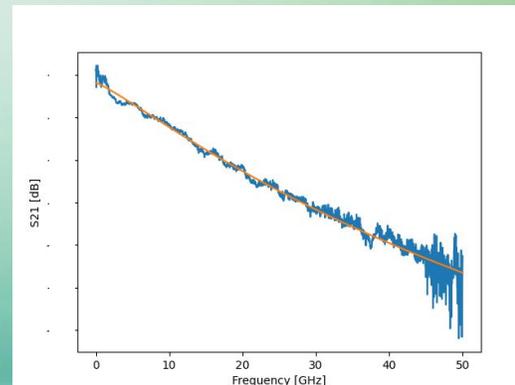
- Top pads are for RF characterization
- Bottom DC pads are for thermally tuning modulator resonance, and monitoring power inside the ring



Passive structure measurement



Thermal phase shifter



Photodetector S21

CM300xi-SiPh Test Executor

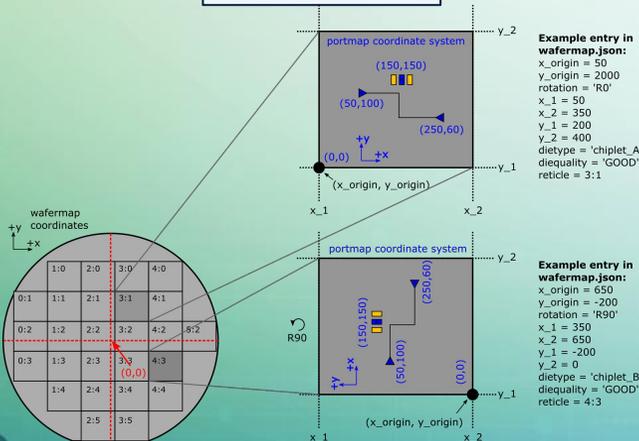
Wafer Map: Coordinates and dimensions of every subdie on wafer
Port Map: Coordinates of every optical port (grating coupler) and electrical port relative to subdie origin
Test Request: A table where each entry specifies a set of optical and/or electrical ports for a test site. It also specifies the measurement routine to execute and its parameters.

Port Map

```

1 # port_map template
2 PD1_gc1:
3   coordinates: [0.0, 0.0]
4   directivity: 'WE' # 'NS', 'EW', 'SN', or 'WE'. Convention: direction light travels from fiber-to-DUT
5   type: 'optical' # 'optical', 'electrical'
6   chip_name: 'chiplet_Y' # Chip name, as specified in the wafer_map
7 PD1_gc2:
8   coordinates: [500.0, 100.0]
9   directivity: 'EW' # 'NS', 'EW', 'SN', or 'WE'. Convention: direction light travels from fiber-to-DUT
10  type: 'optical' # 'optical', 'electrical'
11  chip_name: 'chiplet_Y' # Chip name, as specified in the wafer_map
12 PD2_gc1:
13  coordinates: [0.0, 250.0]
14  directivity: 'WE' # 'NS', 'EW', 'SN', or 'WE'. Convention: direction light travels from fiber-to-DUT
15  type: 'optical' # 'optical', 'electrical'
16  chip_name: 'chiplet_Y' # Chip name, as specified in the wafer_map
17 PD2_gc2:
18  coordinates: [500.0, 350.0]
19  directivity: 'EW' # 'NS', 'EW', 'SN', or 'WE'. Convention: direction light travels from fiber-to-DUT
20  type: 'optical' # 'optical', 'electrical'
21  chip_name: 'chiplet_Y' # Chip name, as specified in the wafer_map
    
```

Wafer Map



Test Executor

Full Test Table

Each entry in full test table contains:

- optical and electrical ports in test site
- chuck coordinates
- hexapod coordinates
- measurement macro to execute
- measurement parameters

Test Request

```

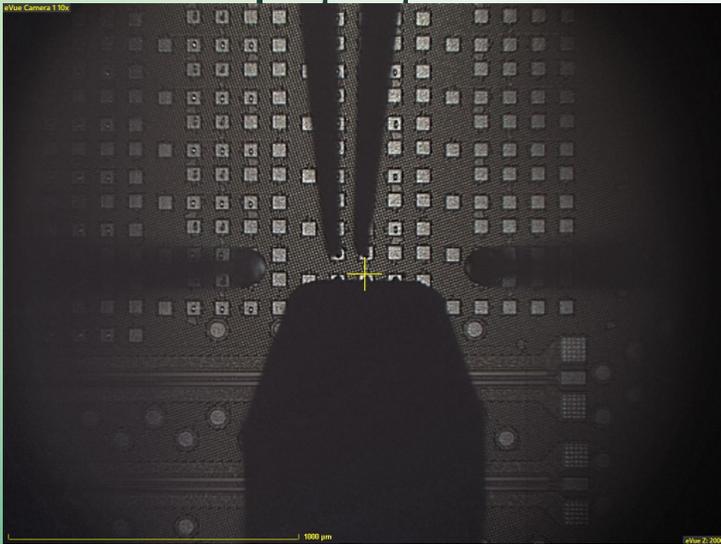
54 test_table:
55 - alignment_parameters: # Can override any defaults from Defaultalignment_parameters, such
56   optical_input_port: 'PD1_gc1' # Key for the corresponding port in "port_map"
57   optical_output_port: 'PD1_gc2' # Key for the corresponding port in "port_map"
58   alignment_light_source: 'laser' # Can be 'laser' or 'sled'. This argument is optional. Defaults t
59   alignment_wavelength: 1290 # The wavelength used for laser alignment. If not specified, the wa
60   electrical_port: # Key for the corresponding port in "port_map"
61     south_pad_1: 'PD1_ground_1'
62     south_pad_2: 'PD1_signal'
63     south_pad_3: 'PD1_ground_2'
64 measurement_macro:
65   measurement_name: 'Insertion loss sweep' # Label. Doesn't affect measurement.
66   macro_executable: 'il_pdl_sweep.py' # Name of the python macro executable
67   macro_recipe: 'il_pdl_sweep.yaml' # YAML file with all parameters needed to run the measurement macro
68   priority: 1
    
```

Improved Test Flow

- **Test throughput is still limited due to multiple factors**
 - Electrical probes need to be manually lowered/lifted. It is not possible to run electrical only or electro-optic tests, along with passive measurements.
 - Time taken to reconfigure and calibrate setup when switching between various types of measurements can be significant (1h ~ half day)
 - Ex. Two tier VNA calibration for RF measurements such as S_{11} (capacitance) or bandwidth (S_{21})
 - Test workflow
 - Set up hardware for passive test
 - Test wafer 1, wafer 2, ...
 - Set up hardware for DC electrical only, and DC electro-optic test
 - Test wafer 1, wafer 2, ...
 - Set up hardware for RF electrical only and RF electro-optic test
 - Test wafer 1, wafer 2, ...

Improved Test Flow

- Motorized positioners for allow us to achieve greater test integration
 - Both RF and DC probes are loaded from south and north side respectively
 - Probe is lifted and retracted when not needed for a given measurement
 - RF calibration is monitored for drift, and periodically re-calibrated on ISS



Optical fibers, DC probe, and RF probe at home site



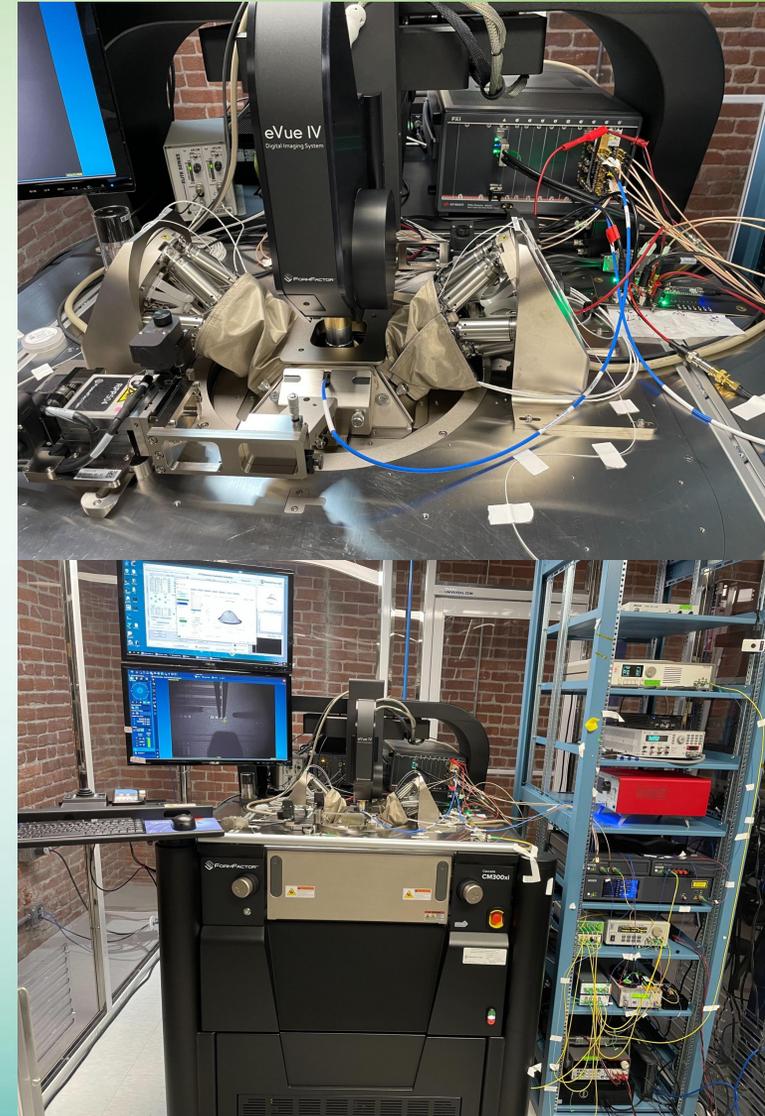
- Optical fibers and DC probe used for measurement
- RF probe lifted and retracted since it is unused



- Optical fibers used for measurement
- DC and RF probe lifted and retracted since they are unused

Summary

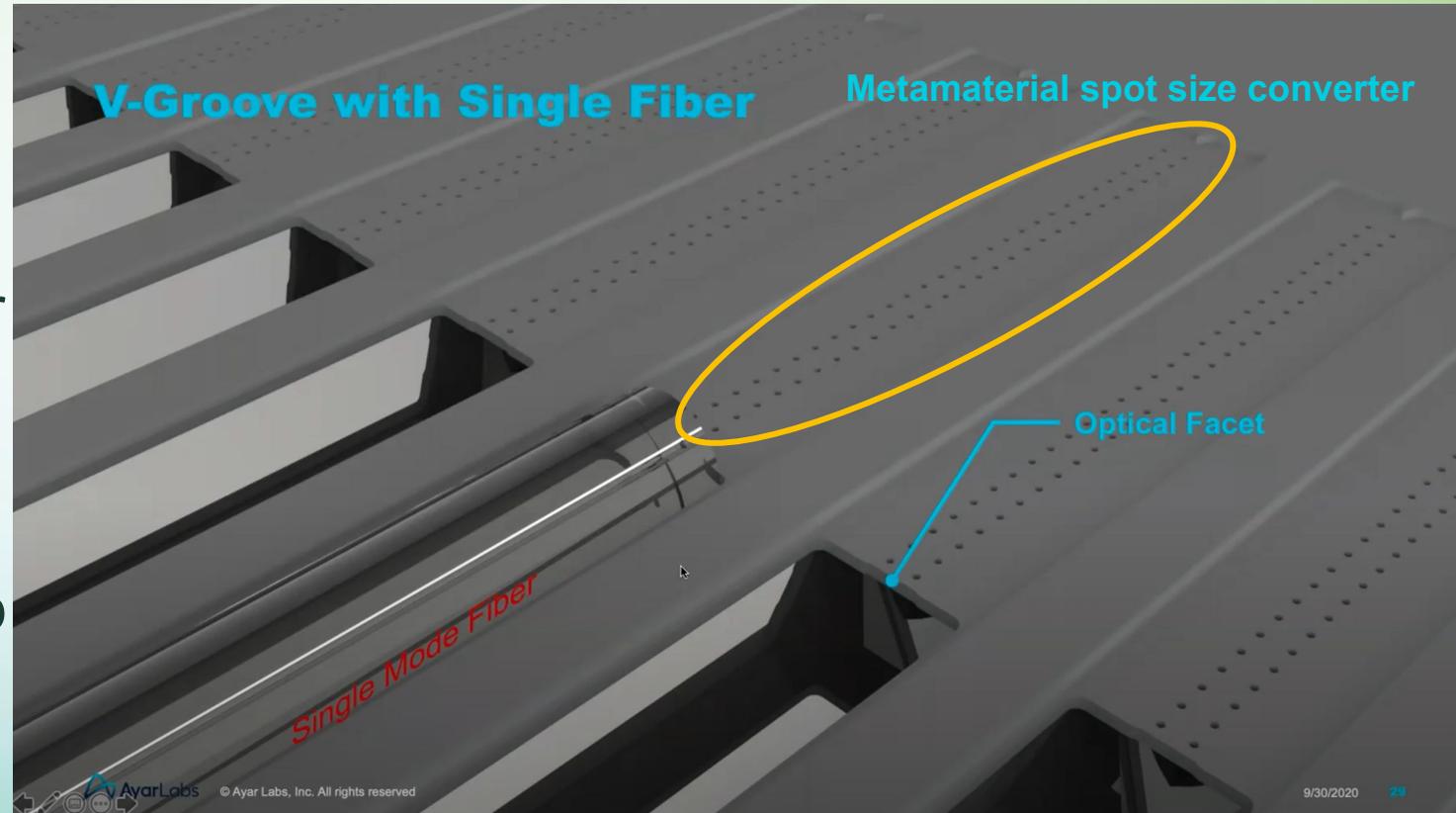
- **CM300xi-SiPh probe station enables us to characterize various electronic/photonic structures at scales needed to obtain statistical distributions with high confidence**
 - These parameters allow us to predict system performance
- **Motorized positioners allow for significantly increased test throughput**
 - Any combination of passive, DC, DC electro-optic, RF, and RF electro-optic measurements can be run over full wafer with no test setup re-configuration and calibration



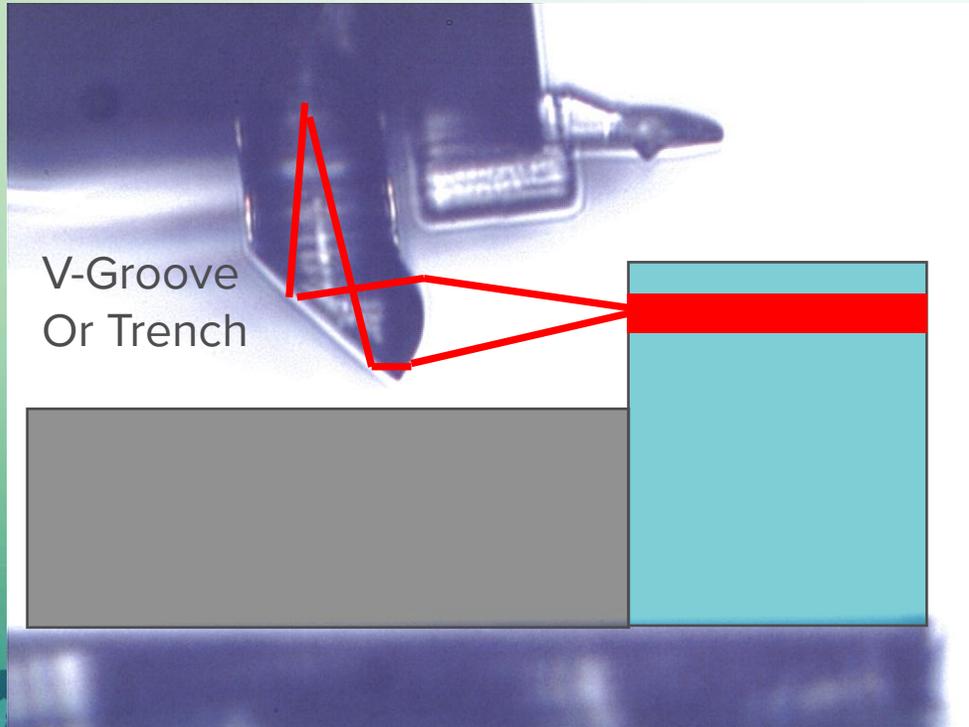
Current Activities and Future Work

Ongoing Test Challenges

- We want to have greater optical and electro-optical functional characterization of the actual TeraPHY™ product chiplet at the wafer level
 - Requires probing at the wafer level through V-grooves for optical connectivity
 - Simultaneously need probe card that can land on all bump locations for electrical connectivity

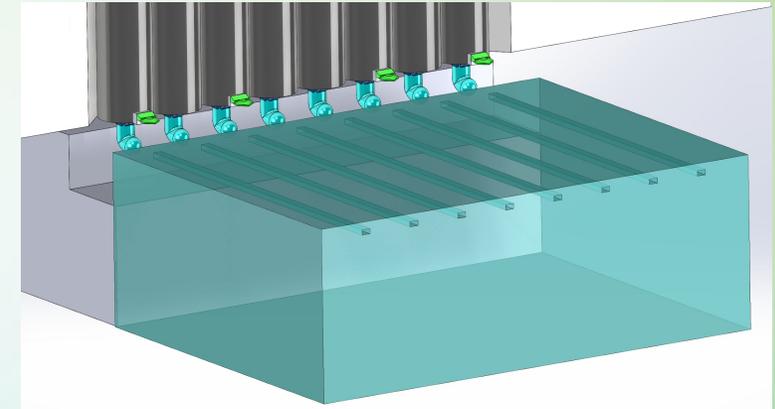


Current Work - Low Loss Wafer Level Edge Coupling

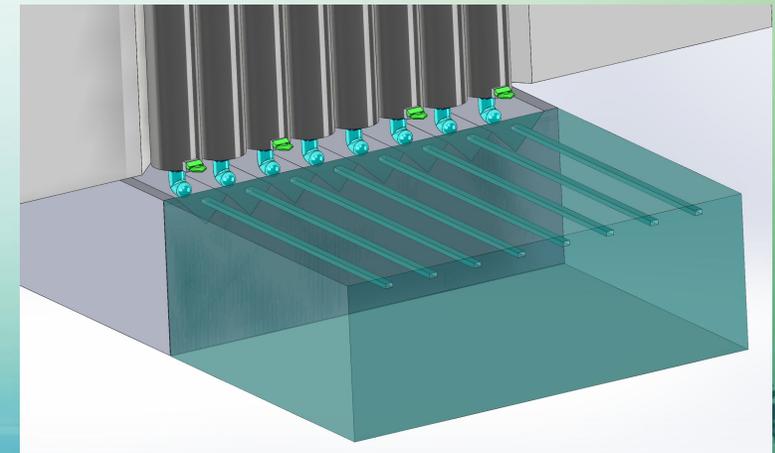


V-Groove
Or Trench

Wafer Level Trench

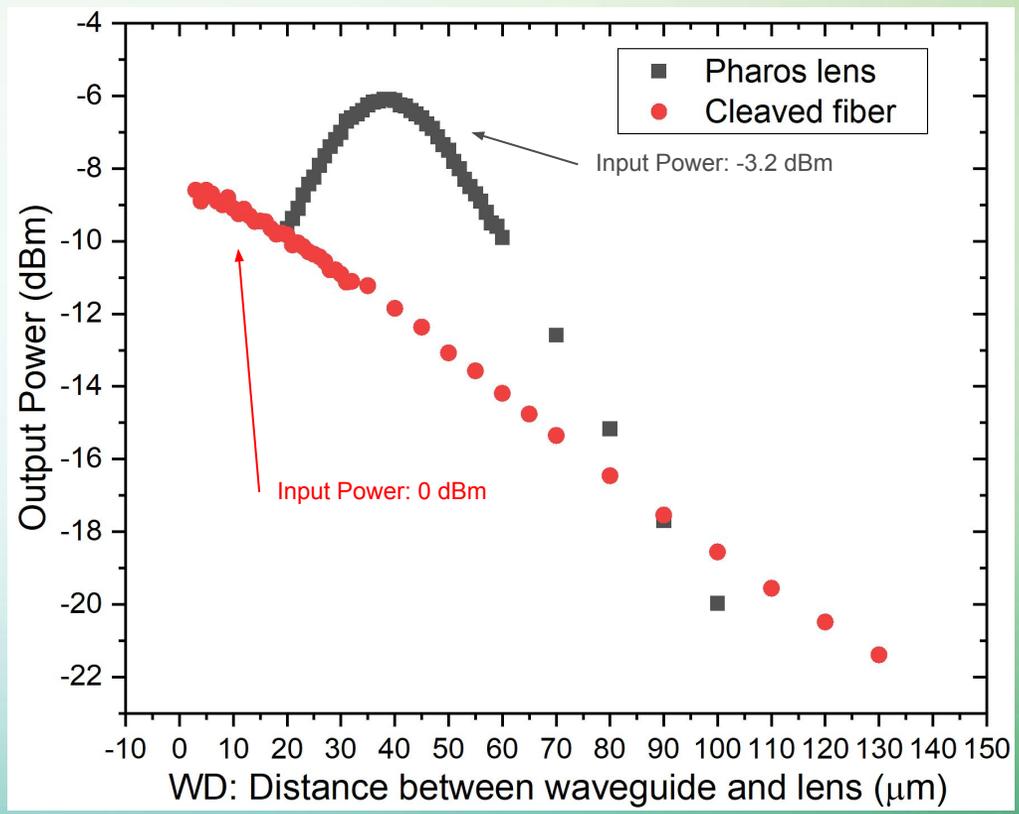
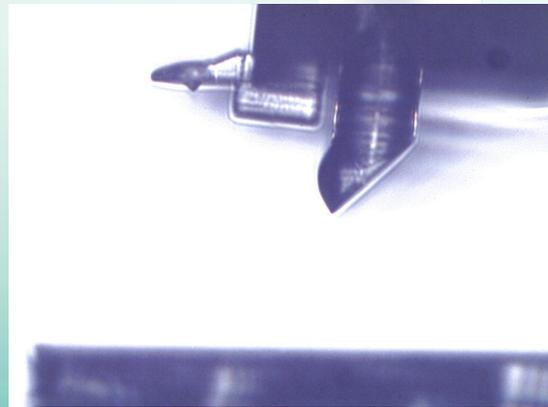
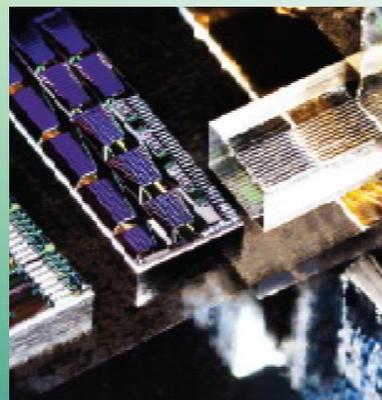
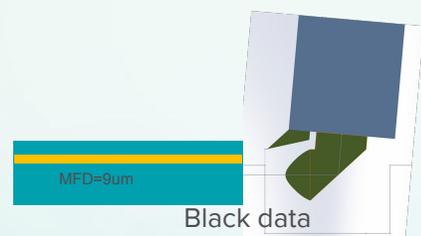


Wafer Level V-Groove



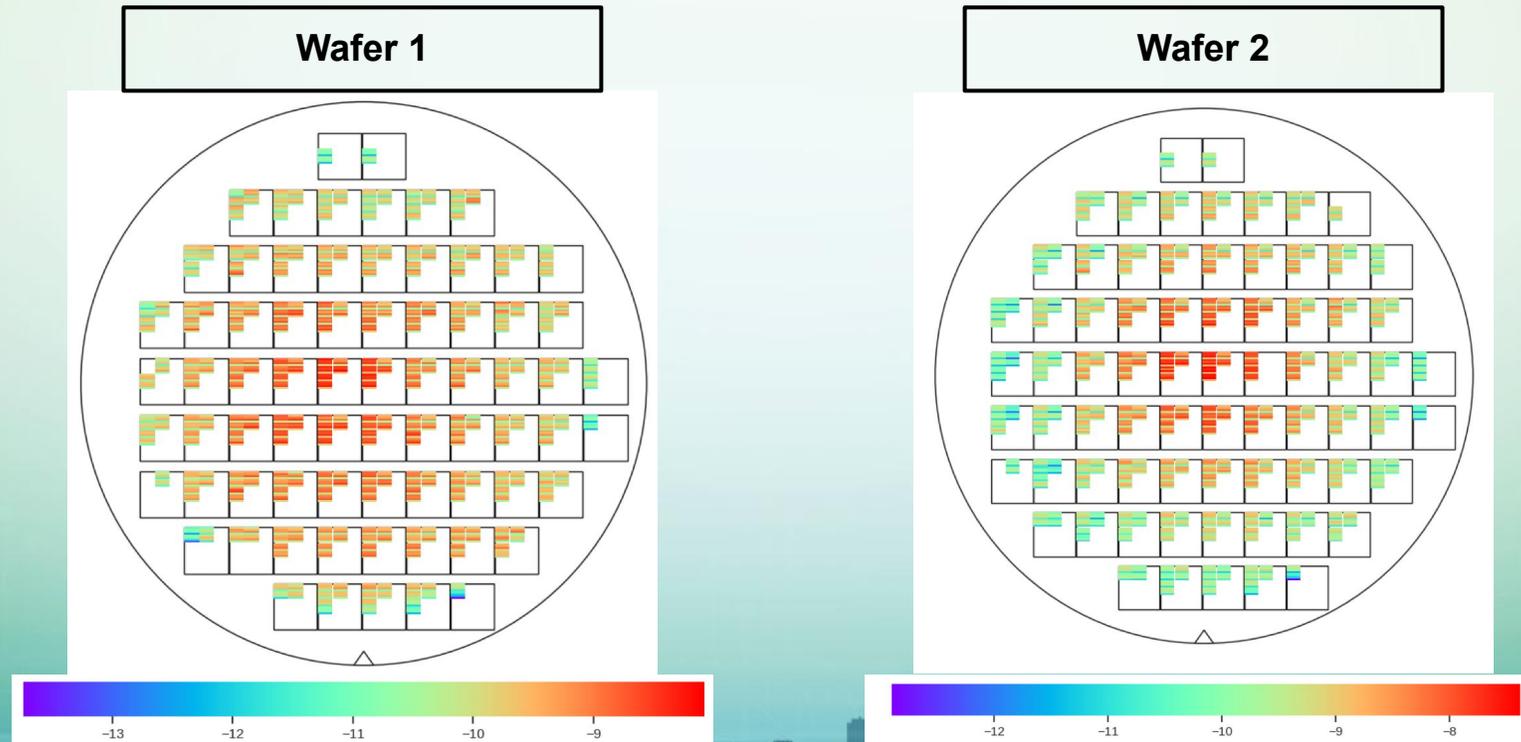
Pharos Low Loss Lens Performance for Edge Coupling

Singulated Chip: Chip1 MFD = 9 μm
 FF Pharos Lens: MFD = 6.0 μm
 Structure: Loopbacks Edge Facet
 Best coupling: WD=5 μm (Cleave fiber array) Power = -8.5 dBm
 Coupling loss is 4.25 dB/facet
 WD=38 μm (**Pharos Lens**) Power = 6.01-3.2 dBm
 Coupling loss is **1.47dB/facet**

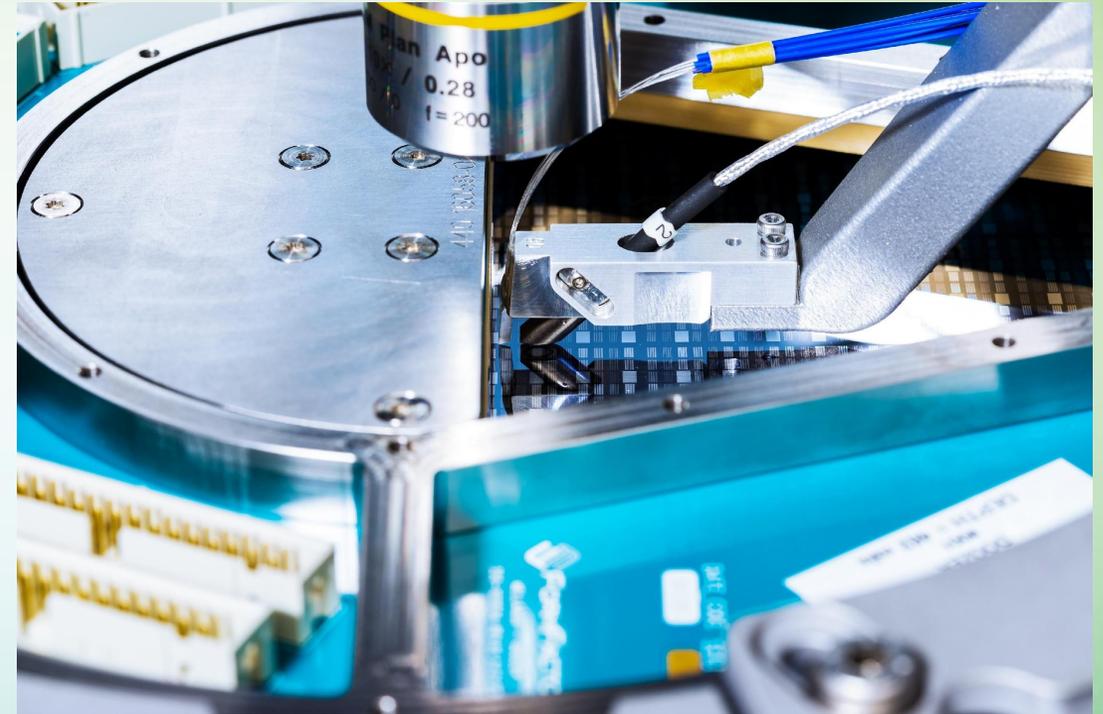
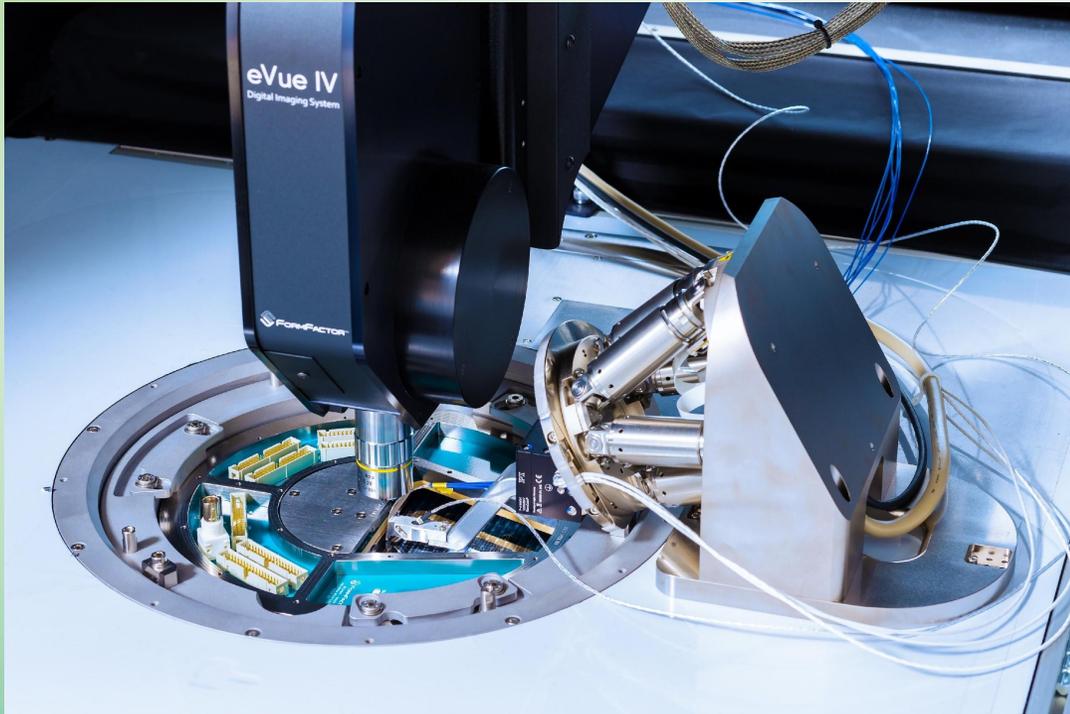


Application of FFI Pharos Technology

- Ayar Labs has performed full wafer measurements on dozens of wafers
- Insertion loss metric is being used as KGD screening criteria



Future Work – FFI Apollo Probe Card with Wafer Level Edge Coupling



Fully Automated Wafer Level Co-Packaged Optics Electrical-Optical Probing

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- **Michael Rust (Sr. Staff Photonic Test Engineer at Ayar Labs)**
- **Neil Sapra (Sr. Photonic Design Engineer at Ayar Labs)**
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- **Joe Frankel (Systems Engineer at FormFactor)**
- **Mike Simmons (Mechanical Design Engineer at FormFactor)**